

Point spread function in a depleted CCD revisited

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The mobility μ is defined as the proportionality constant relating drift velocity v_d to the electric field E :

$$v_d = \mu E \quad (1)$$

It is strongly temperature dependent, For high purity silicon at low fields, Jacobini *et al.*¹ (and, presumably, his reference Conwell²) give

$$\mu(T, E \approx 0) = AT^{-\gamma} , \quad (2)$$

where for holes $A = 1.35 \text{ cm}^2 \text{ K}^\gamma \text{ V}^{-1} \text{ s}^{-1}$ and $\gamma = 2.20$. But v_d is not a linear function of E . We write

$$\mu(T, E) \equiv \mu(T, 0) m(T, E) . \quad (3)$$

Canali *et al.*³ obtain a good fit to experimental data with

$$m(T, E) \approx \left[1 + (E/E_c)^\beta \right]^{-1/\beta} , \quad (4)$$

where, again for holes, $E_c = 1.24 T^{1.68}$, and $\beta = 0.46 T^{0.17}$. As can be seen, E_c is the saturation field at which v_d becomes constant, For the case of the LBNL CCD's, E is typically $(100 \text{ V})/(200 \mu\text{m}) = 5 \text{ kV/cm}$; the nonlinearity is important,

The diffusion constant D is also temperature and field dependent; we define the field correction $\delta(T, E)$ by

$$D(T, E) = D(T, 0) \delta(T, E) . \quad (5)$$

Jacobini *et al.* indicate in their Fig. 13, for holes at 300 K, D decreases by a factor of 0.5₅ between 0 and 5 kV/cm. At that time experimental data were not available for other temperatures, and we have not yet found the relevant data. (Transverse diffusion of holes.) This decrease would decrease the variance by a factor of 0.7₅, nearly canceling the increase via $m(T, E)$. Pending better information, we assume that the correction factor $\delta(T, E)$ is unity.

In thermal equilibrium the Einstein equation relates D and μ : $D/\mu = kT/q$. In the high-field case with "hot" carriers, this equilibrium does not obtain, so we must use $D(T, 0)/\mu(T, 0) = kT/q$.

We are interested in the transverse diffusion of holes produced near the back of an overdepleted CCD (thickness y_D) with electric field $E(y)$ given by Eqns. 4 and 5 in Ref. 4. The variance σ increases by

$$\begin{aligned} d\sigma^2 &= 2D dt \\ &= 2D \frac{dy}{v_d} \\ &= \frac{2kT}{q} \frac{\delta(T, E)}{m(T, E) E(y)} dy \end{aligned} \quad (6)$$

in the time dt that elapses while the hole moves from y to $y + dy$. The variance is thus

$$\sigma^2 = \frac{2kT}{q} \int_0^{y_D} \frac{\delta(T, E)}{m(T, E) E(y)} dy . \quad (7)$$

In the asymptotic case

$$E(y) \rightarrow \langle E(y) \rangle = V_{\text{appl}}/y_D = (V_{\text{sub}} - V_{J'})/y_D ,$$

and

$$\sigma_{\text{asympt}}^2 = \frac{2kT}{q} \frac{\delta(\langle E \rangle, T) y_D^2}{m(\langle E \rangle, T) (V_{\text{sub}} - V_{J'})} . \quad (8)$$

(to be extended after we learn something about $\delta(T, E)$).

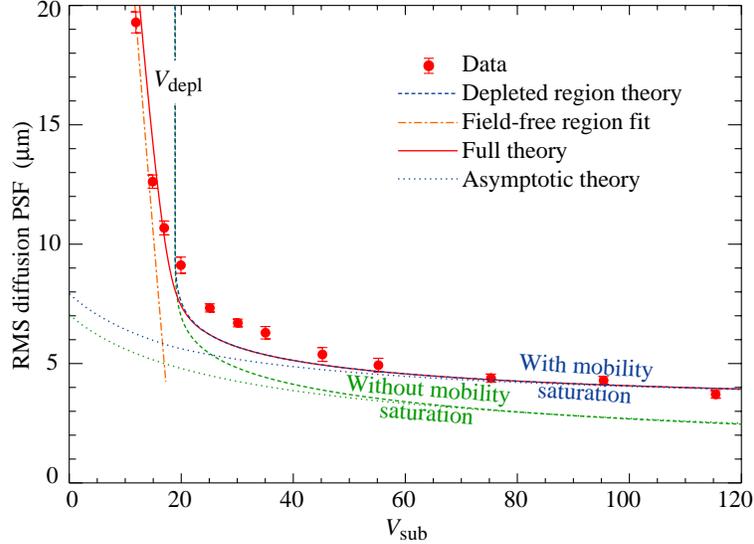


Figure 1: Effect of mobility saturation from Eq. (7). $m(T, E) = 1$ for the case marked “Without mobility saturation,” and with Canali’s form (Eq. (4)) for the case marked “With mobility saturation.” There are no parameters in the theoretical curve except for $V_{J'}$, to which the higher-voltage result is insensitive. In both cases, the diffusion is field-independent, *i.e.*, $\delta(T, E) = 1$. The experimental data were reported in Ref. 5. The discrepant results for 25–50 V are not understood.

References:

1. C. Jacobini *et al.*, “A review of some charge transport properties of silicon,” *Solid-State Electronics* **20**, 77–89 (1977).
2. E. M. Conwell, *High Field Transport in Semiconductors* (Ed. F. Seitz & D. Turnbull), *Solid State Physics*, Suppl. 9, Academic, New York (1967).
3. C. Canali, G. Majni, R. Minder & G. Ottaviani, *IEEE Trans. Electron Dev.* **ED-22**, 1045 (1975).
4. S.E. Holland, D.E. Groom, N.P. Palaio, R. J. Stover, and M. Wei, *IEEE Trans. Electron Dev.* 50 (3), 225–238 (January 2003).
5. J. A. Fairfield, *et al.*, “Improved spatial resolution in thick, fully depleted CCDs with enhanced red sensitivity,” *IEEE Trans. Nucl. Sci.* 53 (6), 3877–3881 (2006).